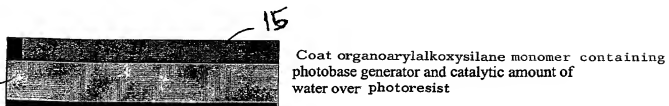


Wafer



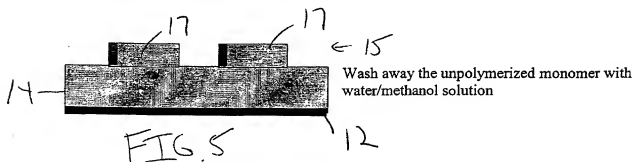
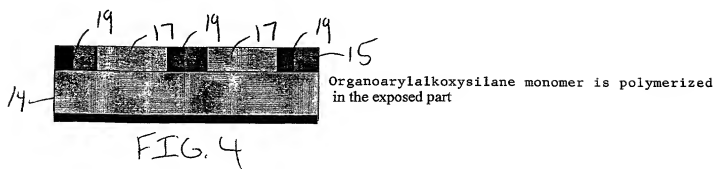
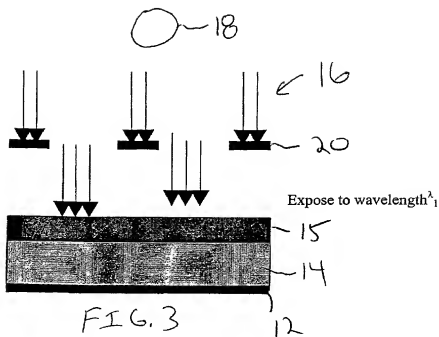
Coat lipophilic photoresist

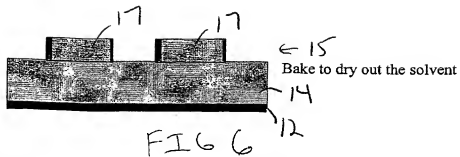
FIG. 1



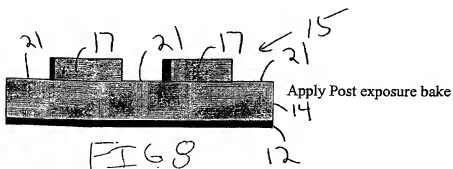
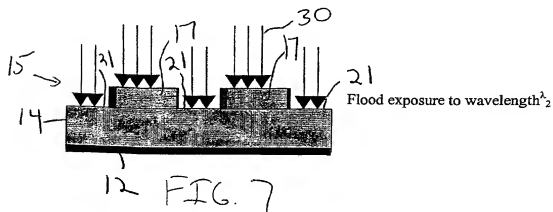
Coat organoarylalkoxysilane monomer containing photobase generator and catalytic amount of water over photoresist

FIG. 2

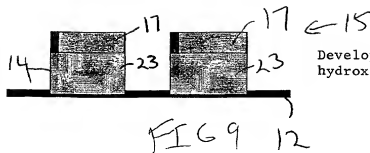




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Develop in tetramethyl ammonium
hydroxide solution

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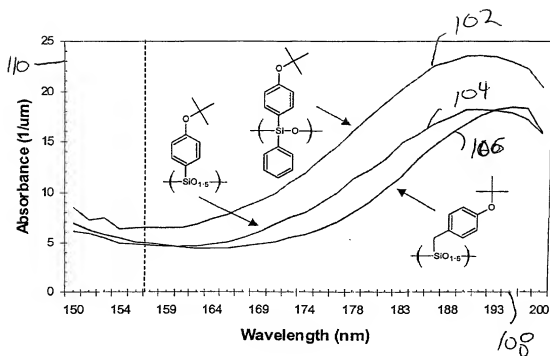


FIGURE 10